



December 20, 2016

Ultratech to Present at Needham Growth Conference on January 10, 2017

SAN JOSE, Calif.--(BUSINESS WIRE)-- Ultratech, Inc. (Nasdaq:UTEK), a leading supplier of lithography, laser-processing and inspection systems used to manufacture semiconductor devices and high-brightness LEDs (HB-LEDs), as well as atomic layer deposition (ALD) systems, today announced that it will present at the 19th Annual Needham Growth Conference on Tuesday, January 10, 2017 at 3:30pm ET at the Lotte New York Palace Hotel in New York, NY.

To listen to the audio webcast of this presentation during or after the event, please visit <http://ir.ultratech.com/>. The replay will be available for 30 days following the event.

About Ultratech: Ultratech, Inc. (Nasdaq: UTEK) designs, builds and markets manufacturing systems for the global technology industry. Founded in 1979, Ultratech serves three core markets: front-end semiconductor, back-end semiconductor, and nanotechnology. The company is the leading supplier of lithography products for bump packaging of integrated circuits and high-brightness LEDs. Ultratech is also the market leader and pioneer of laser spike anneal technology for the production of advanced semiconductor devices. In addition, the company offers solutions leveraging its proprietary coherent gradient sensing (CGS) technology to the semiconductor wafer inspection market and provides atomic layer deposition (ALD) tools to leading research organizations, including academic and industrial institutions. Visit Ultratech online at: www.ultratech.com.

(UTEKF)

View source version on [businesswire.com](http://www.businesswire.com): <http://www.businesswire.com/news/home/20161220005805/en/>

Company Contact:

Ultratech, Inc.

Bruce R. Wright, 408-321-8835

Senior Vice President and CFO

or

Investor Relations:

The Blueshirt Group

Suzanne Schmidt, 415-217-4962

suzanne@blueshirtgroup.com

Source: Ultratech, Inc.

News Provided by Acquire Media